



501.30598CC3

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): MORIOKA, et al

Serial No.: 09/805,188

Filed: March 14, 2001

For: METHOD AND APPARATUS FOR ANALYZING THE STATE OF
GENERATION OF FOREIGN PARTICLES IN
SEMICONDUCTOR FABRICATION PROCESS

Group: 2877

Examiner: T. Nguyen

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G. Stutz
6-18-02

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AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

June 7, 2002

Sir:

The following amendments and remarks are respectfully
submitted in connection with the above-identified application
in response to the Office Action dated April 8, 2002.

IN THE CLAIMS:

Please add the following new claims:

--26. A processing method according to claim 1, further
comprising controlling an operation of the semiconductor
fabrication line in accordance with the data foreign particle
defects detected.

B1

27. A processing method according to claim 1, further
comprising obtaining information of distribution of foreign
particle defects on the substrate and storing the obtained